

Notice of References Cited	Application/Control No. 10/544,783	Applicant(s)/Patent Under Reexamination TERASHIMA ET AL.	
	Examiner PAPE SENE	Art Unit 4135	Page 1 of 1

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*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	A	US-			
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	C	US-			
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NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
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	W	B. Bokhonov et al., "In-situ investigation of the formation of nickel silicides during interaction of single-crystalline and amorphous silicon with nickel" April, 26 th 2001, Journal of Alloys and Compounds, Vol. 319, Pages 187-1195.
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*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.